

LISTING OF THE CLAIMS

1. (Currently amended) A composition comprising:
 - at least one fluoride compound that is free of both organoammonium and amine carboxylate compounds;
 - at least one solvent;
 - at least one surfactant; and
 - water,wherein the composition is saturated with at least one gas selected from the group consisting of nitrogen, argon, helium, oxygen, carbon dioxide, and ozone.
2. (Currently amended) The composition of Claim 1 wherein said at least one gas is selected from the group consisting of nitrogen and; argon, ~~helium, air, oxygen, carbon dioxide, and ozone.~~
3. (Previously presented) The composition of Claim 1 wherein said at least one surfactant is selected from the group consisting of anionic surfactants, cationic surfactants, nonionic surfactants, amphoteric surfactants, and silicone based surfactants.
4. (Previously presented) The composition of Claim 1 wherein the fluoride compounds are selected from the group consisting of ammonium fluoride, ammonium bifluoride or hydrogen fluoride.
5. (Previously presented) The composition of Claim 1 additionally comprising a corrosion inhibitor selected from the group consisting of catechol, t-butyl catechol, pyrogallol, gallic acid and benzotriazole.
6. (Previously presented) The composition of Claim 1 additionally comprising a chelating agent.
7. (Previously presented) The composition of Claim 1 wherein the fluoride compound concentration ranges from about 0.01 percent to about 5 percent by weight.
8. (Previously presented) The composition of Claim 1 wherein said at least one solvent is an organic amide solvent.

9. (Previously presented) The composition of Claim 8 wherein the organic amide solvent concentration range from about 20 percent to about 80 percent by weight.
10. (Previously presented) The composition of Claim 8 additionally comprising up to about 50 weight percent of an organic sulfoxide solvent.
11. (Previously presented) The composition of Claim 10 wherein said organic sulfoxide solvent is dimethyl sulfoxide.
12. (Previously presented) The composition of Claim 1 additionally comprising an alkylamide.
13. (Previously presented) The composition of Claim 1 additionally comprising an alkanolamine.
14. (Previously presented) The composition of Claim 13 wherein the alkanolamine is monoethanolamine.
15. (Previously presented) The composition of Claim 1 wherein the solvent is a lactam.
16. (Previously presented) The composition of Claim 15 wherein the lactam is selected from the group consisting of: a 5-member ring lactam substituted with an alkyl group, a 6-member ring lactam substituted with an alkyl group, a 7-member ring lactam substituted with an alkyl group, a piperidone substituted with an alkyl group, and a piperidone substituted with an alkoxy group.
17. (Previously presented) The composition of Claim 16 wherein any of said alkyl groups comprises from 1 to 5 carbon atoms.
18. (Previously presented) The composition of Claim 16 wherein said alkoxy group comprises from 1 to 5 carbon atoms.
19. (Previously presented) The composition of Claim 16 wherein the lactam is additionally a piperidone selected from the group consisting of dialkyl, and dialkoxy-substituted piperidones.
20. (Previously presented) The composition of Claim 16 wherein the piperidone substituted with an alkyl group is selected from the group consisting of N-methyl piperidone, dimethyl piperidone, N-ethyl piperidone and diethylpiperidone.

21. (Previously presented) The composition of Claim 16 wherein the piperidone substituted with an alkoxy group is selected from the group consisting of: N-methoxy piperidone, dimethoxy piperidone and diethoxy piperidone.
22. (Previously presented) The composition of Claim 1 wherein the water is deionized water.
23. (Previously presented) The composition of Claim 1 suitable for treating a substrate having a surface to which undesired matter adheres.
24. (Currently amended) A composition comprising:
 - at least one hydroxylamine;
 - at least one alkanolamine;
 - at least one surfactant; and
 - at least one solvent,wherein the composition is saturated with at least one gas selected from the group consisting of nitrogen, argon, helium, oxygen, carbon dioxide, and ozone.
25. (Currently amended) The composition of Claim 24 wherein said at least one gas is selected from the group consisting of nitrogen and, argon, ~~helium, air, oxygen, carbon dioxide, and ozone.~~
26. (Previously presented) The composition of Claim 24 wherein said at least one surfactant is selected from the group consisting of anionic surfactants, cationic surfactants, nonionic surfactants, amphoteric surfactants, and silicone based surfactants.
27. (Previously presented) The composition of Claim 24 wherein the hydroxylamine concentration ranges from about 5 to about 50 percent by weight.
28. (Previously presented) The composition of Claim 24 wherein the at least one alkanolamine concentration ranges from about 10 to about 80 percent by weight.
29. (Previously presented) The composition of Claim 24 wherein the alkanol group of the alkanolamine contains from 1 to 5 carbon atoms.
30. (Previously presented) The composition of Claim 24 wherein the alkanolamine is selected from the group consisting of monoalkanolamines, dialkanolamines, and trialkanolamines.

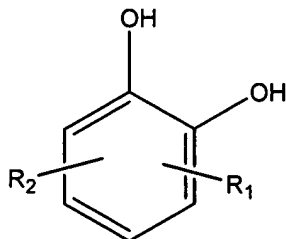
31. (Previously presented) The composition of Claim 24 wherein the alkanolamine has a formula $R_1 R_2-N-CH_2 CH_2-O-CH_2CH_2OH$ wherein R_1 and R_2 independently selected from the group consisting of H, CH_3 , CH_3CH_2 , and CH_2CH_2OH .

32. (Previously presented) The composition of Claim 24 additionally comprising a chelating agent.

33. (Previously presented) The composition of Claim 32 wherein the chelating agent concentration ranges from about 2.5 to about 30 percent by weight.

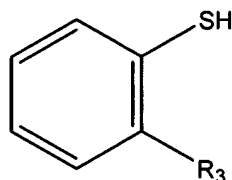
34. (Previously presented) The composition of Claim 32 wherein the chelating agent is selected from the group consisting of:

(1) compounds of formula:



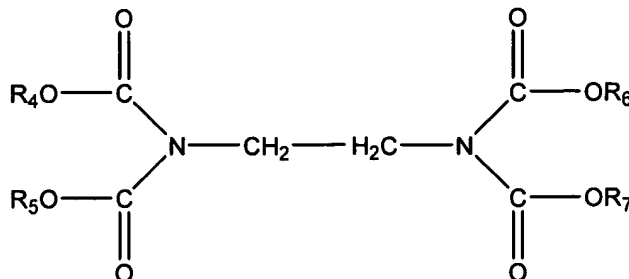
wherein R_1 and R_2 can be either H, t-butyl, OH, or COOH;

(2) compounds of formula:



wherein R_3 is either OH or COOH; and

(3) ethylene diamine tetracarboxylic acid compounds of formula:



wherein R_4 , R_5 , R_6 and R_7 can independently be either H or NH_4^+ .

35. (Previously presented) The composition of Claim 24 wherein the solvent is deionized water.

36. (Previously presented) The composition of Claim 24 wherein the alkanolamine is miscible with the hydroxylamine.
37. (Previously presented) The composition of Claim 24 additionally comprising an acid.
38. (Previously presented) The composition of Claim 37 wherein the acid is present in less than about 10% by weight.
39. (Previously presented) The composition of claim 24 wherein the at least one solvent includes an organic polar solvent.
40. (Previously presented) The composition of claim 39 wherein the organic polar solvent is a glycol, a glycol alkyl ether, an alkyl N-substituted pyrrolidone, ethylene diamine or ethylene triamine.
41. (Previously presented) The composition of Claim 24 suitable for treating a substrate having a surface to which undesired matter adheres.
42. (Currently amended) A composition comprising:
an amine;
a hydroxylamine;
a solvent;
and
a surfactant,
wherein the composition is saturated with a gas selected from the group consisting of nitrogen, argon, helium, oxygen, carbon dioxide, and ozone.
43. (Previously presented) The composition of Claim 42 wherein the amine is selected from the group consisting of choline hydroxide, choline, bis(2-hydroxyethyl) dimethylammonium hydroxide, tris(2-hydroxyethyl) dimethylammonium hydroxide, choline bicarbonate, monoethanolamine, diglycol amine, di(ethylene) triamine, and tri(ethylene) tetramine.
44. (Previously presented) The composition of Claim 42 wherein the amine concentration ranges from about 1 to about 60 percent by weight.
45. (Previously presented) The composition of Claim 42 wherein the amine concentration ranges from about 20 to about 50 percent by weight.

46. (Previously presented) The composition of Claim 42 wherein the amine is choline hydroxide.
47. (Previously presented) The composition of Claim 46 wherein the hydroxylamine is present in a concentration from about 1 to about 10 percent by weight.
48. (Cancelled)
49. (Previously presented) The composition of Claim 42 wherein the hydroxylamine comprises a compound selected from the group consisting of: hydroxylamine salts, hydrazine, hydrazine salts, and an organic derivative of hydroxylamine with the formula R_1R_2N-OH , wherein at least one of R_1 or R_2 is an alkyl group containing 5 or fewer carbons.
50. (Previously presented) The composition of Claim 49 wherein the organic derivative of hydroxylamine is di(ethyl) hydroxylamine or propyl hydroxylamine.
51. (Cancelled)
52. (Currently amended) The composition of Claim 42 wherein the gas is selected from the group consisting of nitrogen, and argon, ~~helium, air, oxygen, carbon dioxide, and ozone.~~
53. (Previously presented) The composition of Claim 42 wherein the surfactant is selected from the group consisting of: anionic surfactants, cationic surfactants, nonionic surfactants, amphoteric surfactants, and silicone based surfactants.
54. (Previously presented) The composition of Claim 42 additionally comprising at least one corrosion inhibitor.
55. (Previously presented) The composition of Claim 54 wherein the corrosion inhibitor is selected from the group consisting of catechol, t-butyl catechol, pyrogallol, gallic acid and benzotriazole.
56. (Previously presented) The composition of Claim 43 wherein the solvent is selected from the group consisting of N-methyl pyrrolidone, γ -butyrolactone, N-methyl piperidone, water and propylene glycol.
57. (Previously presented) The composition of Claim 43 wherein the solvent is water and its concentration ranges from about 60 to about 90 percent by weight.

58. (Previously presented) The composition of Claim 42 wherein the hydroxylamine concentration ranges from about 1 to about 12 percent by weight.
59. (Previously presented) The composition of Claim 54 wherein the corrosion inhibitor is present in a concentration that ranges from about 0.5 to about 5 percent by weight.
60. (Cancelled)
61. (Previously presented) The composition of Claim 42 suitable for treating a substrate having a surface to which undesired matter adheres.
62. (Currently amended) A composition comprising:
periodic acid;
at least one surfactant; and
deionized water,
wherein the composition is saturated with at least one gas selected from the group consisting of nitrogen, argon, helium, oxygen, carbon dioxide, and ozone.
63. (Previously presented) The composition of Claim 62 additionally comprising at least one base selected from the group consisting of potassium hydroxide, sodium hydroxide, ammonium hydroxide, tetramethylammonium hydroxide, trimethyl(2-hydroxyethyl)ammonium hydroxide (choline), and choline derivatives.
64. (Previously presented) The composition of Claim 62 additionally comprising a corrosion inhibitor selected from the group consisting of catechol, t-butyl catechol, pyrogallol, gallic acid and benzotriazole.
65. (Currently amended) The composition of Claim 62 wherein the gas is selected from the group consisting of nitrogen, and argon, ~~helium, air, oxygen, carbon dioxide, and ozone.~~
66. (Previously presented) The composition of Claim 62 wherein the surfactant is selected from the group consisting of anionic surfactants, cationic surfactants, nonionic surfactants, amphoteric surfactants, and silicone based surfactants.
67. (Previously presented) The composition of Claim 62 suitable for treating a substrate having a surface to which undesired matter adheres.
68. (Currently amended) A composition for treating a surface of a substrate comprising:

at least one amine;

at least one acid selected from the group consisting of citric acid, formic acid, acetic acid, propionic acid, n-butyric acid, iso-butyric acid, benzoic acid, ascorbic acid, gluconic acid, malic acid, malonic acid, oxalic acid, succinic acid, tartaric acid, and gallic acid;

at least one surfactant selected from the group consisting of anionic surfactants, cationic surfactants, nonionic surfactants, amphoteric surfactants, and silicone based surfactants, wherein at least one surfactant is suitable to allow foaming;

at least one chelating agent selected from the group consisting of ethylenediaminetetraacetic acid, citric acid, oximes, lactic acid, 8-hydroxy quinoline, salicylic acid, and salicyclalldoxime;

at least one corrosion inhibitor selected from the group consisting of catechol, t-butyl catechol, pyrogallol, gallic acid and benzotriazole; and

deionized water, wherein the composition is saturated with at least one gas selected from the group consisting of nitrogen, argon, helium, ~~air~~, oxygen, carbon dioxide, and ozone.

69. (Previously presented) The composition of Claim 68 wherein the amine is selected from the group consisting of hydroxylamine, hydroxylamine salts, hydrazine, hydrazine salts, quaternary amines, and ammonium hydroxide.

70. (Previously presented) The composition of Claim 68 wherein the concentration of amines is sufficient to buffer the composition to a pH of 4 to 6.

71. (Previously presented) The composition of Claim 68 wherein the concentration of acid ranges from about 2.0 to about 11 percent by weight.

72. (Previously presented) The composition of Claim 68 wherein the concentration of chelating agents is less than or equal to about 1.0 percent by weight.

73. (Previously presented) The composition of Claim 69 wherein the concentration of surfactants ranges from about 0.05 to about 3.0 percent by weight.

74. (Previously presented) The composition of Claim 68 suitable for treating a substrate to which undesired matter adheres.
75. (Currently amended) A composition comprising: a surfactant; deionized water; and a component selected from the group consisting of: a fluoride other than HF; a hydroxylamine; an amine; and periodic acid; wherein the amine is present with a polar solvent and the amine is selected from the group consisting of: choline hydroxide; bis(2-hydroxyethyl) dimethylammonium hydroxide; diglycol amine; di(ethylene) triamine; tri(ethylene) tetramine; and choline bicarbonate, wherein the composition is saturated with a gas selected from the group consisting of nitrogen, argon, helium, oxygen, carbon dioxide, and ozone.
76. (Previously presented) The composition of claim 75 additionally comprising a corrosion inhibitor.
77. (Previously presented) The composition of claim 76 additionally comprising a chelating agent.
78. (Previously presented) The composition of claim 76 additionally comprising a non-aqueous solvent.
79. (Currently amended) A composition comprising:
an amine;
a first solvent;
a second solvent;
and
at least one surfactant, wherein the composition is saturated with at least one gas selected from the group consisting of nitrogen, argon, helium, oxygen, carbon dioxide, and ozone.
80. (Previously presented) The composition of Claim 79 wherein the amine is selected from the group consisting of: morpholine, monoethanolamine, diglycol amine, di(ethylene triamine), tri(ethylene) tetramine, 2-methylamine ethanol, choline hydroxide, bis(2-hydroxyethyl) dimethyl-ammonium hydroxide, tris(2-hydroxyethyl)dimethylammonium hydroxide, and choline bicarbonate.

81. (Previously presented) The composition of Claim 80 wherein the amine is morpholine and has a concentration from about 40 to about 60 percent by weight.
82. (Previously presented) The composition of Claim 80 wherein the amine is 2-methylamine ethanol and has a concentration from about 1 to about 10 percent by weight.
83. (Previously presented) The composition of Claim 80 wherein the amine is choline hydroxide and has a concentration from about 10 to about 50 percent by weight.
84. (Previously presented) The composition of Claim 79 wherein the first solvent is a polar solvent.
85. (Previously presented) The composition of Claim 84 wherein the polar solvent is selected from the group consisting of: N-(2-hydroxyethyl)-2-pyrrolidone; dimethyl sulfoxide; di(methyl) formamide; and di(methyl) acetamide.
86. (Previously presented) The composition of claim 85 wherein the polar solvent is N-methyl pyrrolidone and is present in a concentration of about 20 – 50% by weight.
87. (Previously presented) The composition of Claim 84 wherein the polar solvent is selected from the group consisting of: γ -butyrolactone; ethylene carbonate; propylene carbonate; di(propylene glycol); monomethyl ether; ethyl lactate; propyl lactate; butyl lactate; and propylene glycol.
88. (Previously presented) The composition of claim 87 wherein the polar solvent is propylene glycol and is present in a concentration of about 20 – 80% by weight.
89. (Previously presented) The composition of Claim 79 wherein the second solvent is a polar solvent.
90. (Previously presented) The composition of Claim 89 wherein the polar solvent is selected from the group consisting of: γ -butyrolactone; ethylene carbonate; propylene carbonate; di(propyleneglycol) monomethyl ether; ethyl lactate; propyl lactate; butyl lactate; and propylene glycol.
91. (Previously presented) The composition of Claim 90 wherein the polar solvent is γ -butyrolactone and is present in a concentration from about 5 to about 25 percent by weight.

92. (Previously presented) The composition of Claim 89 wherein the polar solvent is selected from the group consisting of: N-methyl pyrrolidone; N-(2-hydroxyethyl)-2-pyrrolidone; dimethyl sulfoxide; di(methyl) formamide; and di(methyl) acetamide.
93. (Previously presented) The composition of Claim 92 wherein the polar solvent is dimethyl sulfoxide and is present in a concentration from about 20 to about 50 percent by weight.
94. (Previously presented) The composition of Claim 79 wherein the second solvent is water in a concentration of about 25% by weight.
95. (Currently amended) The composition of Claim 79 wherein the gas is selected from the group consisting of nitrogen, and argon, ~~helium, air, oxygen, carbon dioxide, and ozone.~~
96. (Previously presented) The composition of Claim 79 wherein the surfactant is selected from the group consisting of: anionic surfactants, cationic surfactants, nonionic surfactants, amphoteric surfactants, and silicone based surfactants.
97. (Previously presented) The composition of Claim 79 additionally comprising at least one corrosion inhibitor.
98. (Previously presented) The composition of Claim 97 wherein the corrosion inhibitor is selected from the group consisting of catechol, t-butyl catechol, pyrogallol, gallic acid and benzotriazole.
99. (Previously presented) The composition of Claim 97 wherein the corrosion inhibitor is present in an amount of up to about 5% by weight.
100. (Previously presented) The composition of Claim 79 suitable for treating a substrate having a surface to which undesired matter adheres.
101. (Previously presented) A method of treating a substrate to remove undesired matter, comprising:
causing the composition of any one of claims 1, 24, 42, 62, 68, 75, and 79 to foam;
and
contacting the substrate with the foam.

102. (Previously presented) A method of cleaning a surface of a substrate, comprising:
placing the substrate and a liquid composition in a treatment vessel; and
creating a foam by:
introducing a gas under pressure into the liquid composition; or
depressurizing the vessel;
contacting the surface of the substrate with said foam,
wherein the liquid composition comprises:
at least one solvent;
at least one surfactant; and
at least one agent selected from the group consisting of:
a fluoride; HDA and an alkanolamine; HDA and an amine; periodic
acid; a fluoride other than HF; choline; and choline hydroxide.
103. (Previously presented) A method of cleaning a surface of a substrate, comprising:
placing the substrate and a composition in a treatment vessel;
creating a foam by depressurizing the vessel; and
contacting the surface of the substrate with said foam,
wherein the composition is according to any one of claims 1, 24, 42, 62, 68, 75, and
79.